| Form PTO 1449 (Rev. 2-32) U.S. Department of Commerce Patent and Trademark Office | | | | | | Atty. Docket No. 034299-268 | | Serial No. 09/600,590 | | |
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| PE Antormation Disclosure Statement by Applicant | | | | | Applicant: Aspar et al. Filed: Group: | | | | | |
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